

GAS SUPPLY METHOD, SEMICONDUCTOR DEVICE MANUFACTURING METHOD,
SUBSTRATE PROCESSING APPARATUS AND PROGRAM, AND FLOW RATE
CONTROLLER

ABSTRACT

The present invention includes a first process of supplying a gas to a container while controlling a flow rate of the gas by regulating valve opening, and a second process of regulating the valve opening on the basis of an internal pressure of the container and supplying the gas to the container.

Fig. 5